

## **MASK INSPECTION PROCESS ACCOUNTING FOR MASK WRITER PROXIMITY CORRECTION**

### **Abstract of the Disclosure**

A mask inspection method and system. Provided is a mask fabrication database  
5 describing geometrical shapes  $S$  to be printed as part of a mask pattern on a reticle to fabricate a  
mask through use of a mask fabrication tooling. The shapes  $S$  appear on the mask as shapes  $S'$   
upon being printed. At least one of the shapes  $S'$  may be geometrically distorted relative to a  
corresponding at least one of the shapes  $S$  due to a lack of precision in the mask fabrication  
tooling. Also provided is a mask inspection database to be used for inspecting the mask after the  
10 mask has been fabricated by the mask fabrication tooling. The mask inspection database  
describes shapes  $S''$  approximating the shapes  $S'$ . A geometric distortion between the shapes  $S'$   
and  $S''$  is less than a corresponding geometric distortion between the shapes  $S'$  and  $S$ .